

REMARKS

Reconsideration and the timely allowance of the pending claims, in view of the following remarks, are respectfully requested.

In the pending Office Action, the Examiner rejected claims 1-2, under 35 U.S.C. §102(b), as allegedly being anticipated by Grover '917 (U.S. Pat. No. 5,795,917); rejected claims 3-5, under 35 U.S.C. §103(a), as allegedly being unpatentable over Grover '917 in view of Akahori '538 (EP 1148538); rejected claims 6-8, 10-12, 14, and 16-17 and 4-5, under 35 U.S.C. §102(b), as allegedly being anticipated by Kido '111 (EP 1061111); rejected claim 13, under 35 U.S.C. §103(a), as allegedly being unpatentable over Kido '111 in view of Grover '917; rejected claims 9 and 15, under 35 U.S.C. §103(a), as allegedly being unpatentable over Kido '111 in view of Akahori '538.

By this Amendment, claims 1-17 have been amended for form and clarity and no new matter has been added. As such, claims 1-17, are currently presented for examination of which claims 1, 6, and 13 are independent.

Insofar as the rejections are still deemed relevant in view of the claim changes, Applicants traverse the §102 and §103 rejections for the following reasons:

I. Rejections Under §102 & §103.

As noted above, independent claim 1 is directed to a chemical-mechanical-polishing slurry composition and includes the following features:

- (1) the slurry composition includes ceria polishing particles, a dispersing agent, and an anionic additive; and
- (2) the ceria polishing particles are polyhedron.

These features are amply supported by the embodiments disclosed in the written description. (See, Specification: page 13, line 23 – page 14, line 13). By way of example, the disclosed embodiments provide that, because the ceria polishing particles of the present

invention are polyhedron, the ceria polishing particles can have plane-contact capability to the wafers during polishing. Therefore, the ceria polishing particles are capable of accelerating the ablating rate (i.e., polishing rate). This is to be contrasted with conventional spherical abrasives (e.g., fumed silica abrasives) which have point contact capability to the wafers during polishing and cannot accelerate the ablating rate.

With this said, Applicants respectfully submit that, despite the Examiner's contentions, none of the asserted references, whether taken alone or in reasonable combination, remotely suggest each and every element of claim 1 including, for example, the features identified above. Simply put, there is absolutely nothing in any of the references, namely, Grover '917, Kido '111, and Akahori '538, that suggests that the *ceria polishing particles are polyhedron*.

Thus, for at least these reasons, Applicants submit that claim 1 is patentable over the asserted references. And, because claims 2-5 depend from claim 1, claims 2-5 are patentable at least by virtue of dependency as well as for their additional recitations.

Moreover, because independent claims 6 and 13 recite similar patentable features as claim 1, claims 6 and 13 are patentable for at least the reasons presented relative to claim 1. And, because claims 7-12 and claims 14-17 depend from claims 6 and 13, respectively, claims 7-12 and claims 14-17 are patentable at least by virtue of dependency as well as for their additional recitations.

Accordingly, the immediate withdrawal of the §102 and §103 rejections of claims 1-17 is respectfully requested.

CONCLUSION

Having addressed each of the foregoing rejections, it is respectfully submitted that a full and complete response has been made to the outstanding Office Action and, as such, the application is in condition for allowance. Notice to that effect is respectfully requested.

If the Examiner believes, for any reason, that personal communication will expedite prosecution of this application, the Examiner is invited to telephone the undersigned at the number provided.

Please charge any fees associated with the submission of this paper to Deposit Account Number 033975. The Commissioner for Patents is also authorized to credit any over payments to the above-referenced Deposit Account.

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Respectfully Submitted,

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